## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:	) CONFIRMATION NO.: 3543
Hiroki OHNO, et al.	)
U.S. Serial No.: 10/594,549	) Group Art Unit: 1792
Filed: September 27, 2006	) Examiner: Bibi S. Carrillo

For: SUBSTRATE CLEANING METHOD, SUBSTRATE CLEANING EQUIPMENT.

COMPUTER PROGRAM, AND PROGRAM RECORDING MEDIUM

## RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

A response to the Office Action mailed October 29, 2009 is due by November 29, 2009. The Action required restriction between two patentably distinct inventions.

Applicants hereby elect <u>Group I of claims 1-17 and 21-24</u>, drawn to a substrate cleaning method, for examination in this application. Applicants advise that no change in the inventorship of the application will be required by the eventual cancellation of non-elected claims.

Applicants reserve the right to file divisional application(s) for the non-elected claims in due course.

It is submitted that this application now is in condition for examination on the merits and early action in that regard is solicited.

Respectfully submitted,

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